


providing a temperature controlling fluid from a source to each of the plurality of workstations,

monitoring the temperature at each individual workstation and
independently controlling heating of the fluid provided to each individual station
in accordance with information comprising a differential between the predetermined
temperature and a temperature at each of the respective workstations.

28. (new) The process of claim 27 further comprising the step of transporting an amount
of the fluid to a workstation through a bypass conduit that bypasses a heater
corresponding to the workstation.

29. (new) A temperature control system for individually regulating the temperatures of a
plurality of semiconductor workstations, the temperature control system comprising:

a central source of a temperature regulating fluid in flow communication with
each of the plurality of workstations for transporting fluid to each workstation and
independently controlling temperature at each workstation, and

a plurality of heaters, each heater being associated with a workstation in a manner
effective to heat the fluid transported to one of the individual workstations from the
central source, whereby the temperature of the fluid provided to each workstation is
controlled independently of fluid transported to other workstations of the system.

30. (new) The temperature control system of claim 29, wherein each workstation is
independently controlled at a desired temperature, and wherein the fluid at the central
source is at a temperature that is lower than any of the desired temperatures.

31. (new) The temperature control system of claim 29, further comprising a bypass
conduit for at least one of the workstations allowing the fluid transported to said
workstation to bypass the heater corresponding to the particular workstation.